

EAST

3-2-2	1st	Boys	1st	Car
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1454 000000 00

IV = 0.6897 (estimated)

5114982
5260343
5462797
5578362
5699960
5821316
6020397
6095902
6362107
6454634
6477926
20020045297
20030069321
20030105209
5900164
6022269

Ⓢ Pending

Active

Q 13: (21) {"5114982"} or {"5151343"} or {"5162

Failed

★ BRG loc ★ RSP loc ★ In Name ★ By Tax ★ 11/1/88

	U	I	Document ID	Issue Date	Pages	Title	Current OR	Current Ref	Retrieval C	Inventor	S	C	P	Ref	Ref
1			US 20030105209 A1	20030612	12	Polishing pad	451/527			Hishiki, Seigo	P				
2			US 20030069321 A1	20020410	12	High modulus, impact resistant foams for	521/159	521/137; 521/170;		Lin, Nendy Wen-Ling et al.	P				
3			US 20020049297 A1	20020425	9	Urethane composition for sheet transport roll and	528/76			Suzuki, Satoshi et al.	P				
4			US 6477926 B1	20021112	16	Polishing pad	451/526	51/296		Swisher, Robert G. et al.	P				
5			US 6454634 B1	20020924	6	Polishing pads for chemical mechanical planarization	451/41	451/285; 451/36;		James, David B. et al.	P				
6			US 6362107 B1	20020326	10	Polishing pad and polishing device	436/692	216/2; 216/38;		Shiro, Rumiya et al.	P				
7			US 6095902 A	20000801	3	Polyether-polyester polyurethane polishing pads	451/36	451/120; 451/37;		Reinhardt, Heinz F.	P				
8			US 6022268 A	20000208	7	Polishing pads and methods relating thereto	451/548	451/41; 51/296		Roberts, John V. H. et al.	P				
9			US 6020387 A	20000201	7	Low density polymers and methods of making and using	521/57	521/122; 521/123;		Downey, William J. et al.	P				
10			US 5900164 A	19990504	15	Method for planarizing a semiconductor device surface	216/58	216/89		Budinger, William D. et al.	P				
11			US 5821316 A	19981013	7	Polyurethane prepolymers for making elastomers having	528/64	560/115; 560/158;		Quay, Jeffrey Raymond et al.	P				